Progress with 100 mm Diameter In_{.53}Ga_{.47}As/InP Wafer Processing

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*We gratefully acknowledge the NIST-ATP Program for their support



WHY 100 mm InGaAs/InP?

- Who Needs It??
- For What??



WHY 100 mm InGaAs/InP

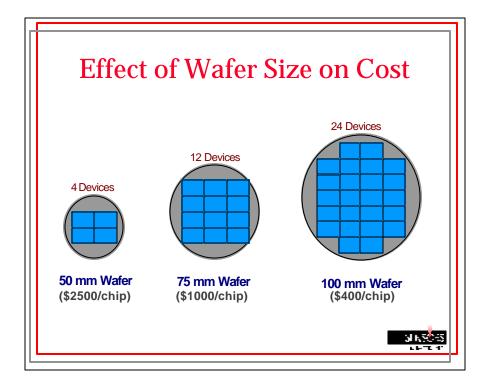
- Near-Infrared Imaging: >\$1B
 - chip size is 13x18 mm
- Wavelength Division Multiplexing: >\$1B
 - chip size is 6x15 mm
- 6x Cost Reduction from 50 mm

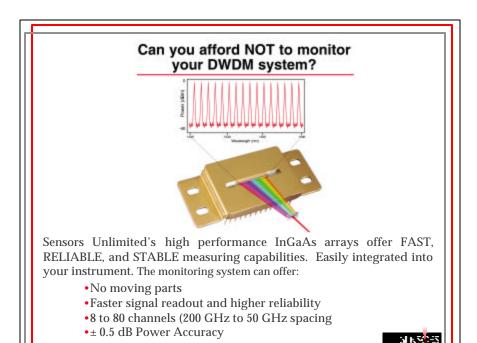


Why 100 mm (4 inch) InP?

- Save Money
- Increase Yield
- Enable New Products
- Motivated by NIST-ATP Program
- Synergistic with USAF Title III Program











Camouflage Under Low Light Level Illumination





Visible CCD

InGaAs FPA @ 10°C

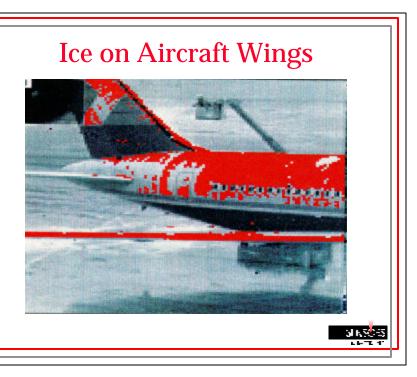
Threshold for detection ≈6 mLux (bright starlight)



Transportation/Ice Detection

- Air and Car Transportation
- Significant Positive Impact on Safety
- Over 10,000 Airports
- Over 1,000,000 Bridges and Roadways
- In Year 2000, SUI Sales Projections =
 .02% of Airports and Bridges





Other Focal Plane Array Programs

• DARPA-Microcamera



- Miniature camera for robotics applications
- < 200 gm (goal 120 gm)
- Built-in 1.55 μm laser designator



GOALS

- Demonstrate a 100 mm diameter
 InGaAs/InP manufacturing process
 - good quality substrates
 - uniform epitaxy
 - process tools
 - → >50% yield of camera chips



Conclusions (as of Nov, 1999)

- **GOOD** quality 100 mm S-InP substrates
- GOOD quality InGaAs/InP photodiodes on 75 mm S-doped substrates
- "Spin-On" zinc diffusion works
- We expect the program to **SUCCEED**



Summary of Results InGaAs/InP Photodiode Arrays

